



Leibniz Institute
for high
performance
microelectronics

Characterization and Modeling of SET Effects in Standard Combinational Cells

Marko Andjelkovic

IHP – Institute for High Performance Microelectronics, Frankfurt (Oder), Germany

TWIN-RELECT Scientific Workshop

University of Thessaly, Volos, Greece

21-23 July, 2025.

Outline



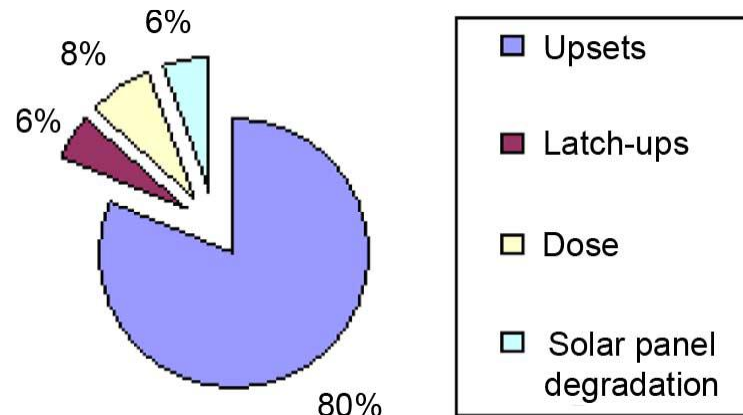
1. **Introduction to SET Effects**
2. **SET Characterization Methodology**
3. **SET Characterization for IHP's 130nm Standard Cells**
4. **SET Sensitivity Prediction with Fitting Models**
5. **SET Sensitivity Prediction with ML Models**
6. **Conclusion**

1. Introduction to SET Effects

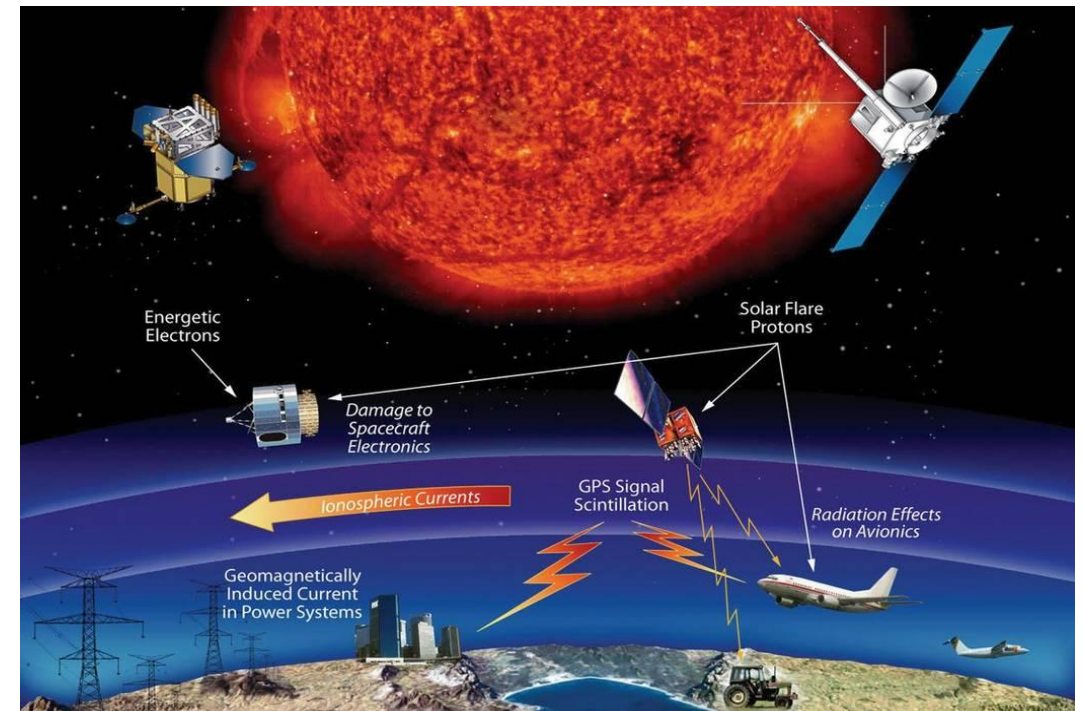


—○ Soft errors are a major reliability issue for digital circuits employed in space applications

- Manifested as bit-flips, resulting in data loss and system malfunction
- Caused by energetic particles such as heavy ions, neutrons, protons



Source: R. Ecoffet, Overview of In-Orbit Radiation Induced Spacecraft Anomalies, IEEE Transactions on Nuclear Science, 2013.



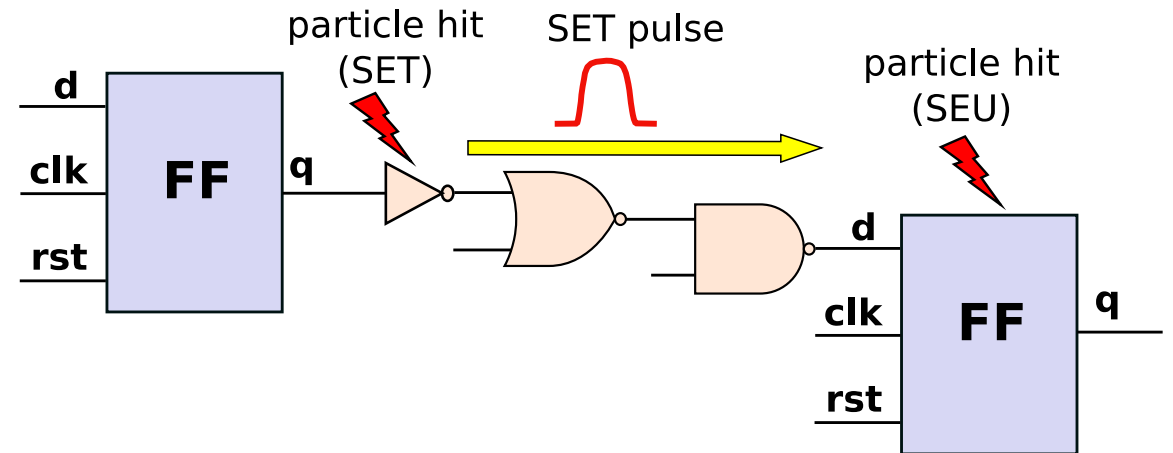
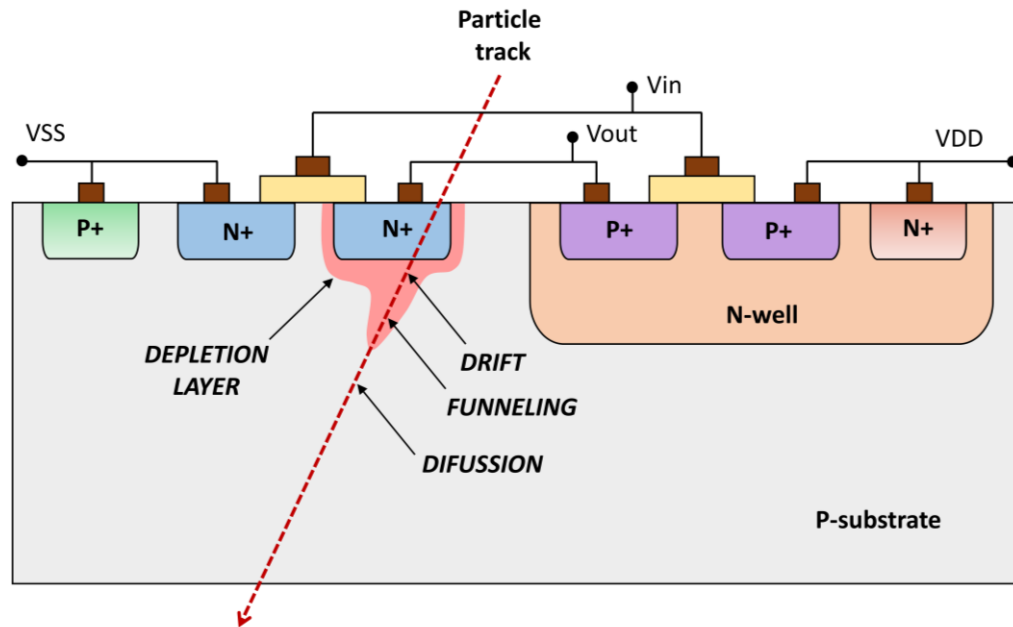
[Source: NASA]

1. Introduction to SET Effects



How soft errors occur?

- Particle hits a storage element, resulting in a bit-flip (**Single Event Upset - SEU**)
- Particle hits a combinational element, resulting in a voltage glitch (**Single Event Transient - SET**), which may propagate to one or more storage elements and cause one or more bit-flips

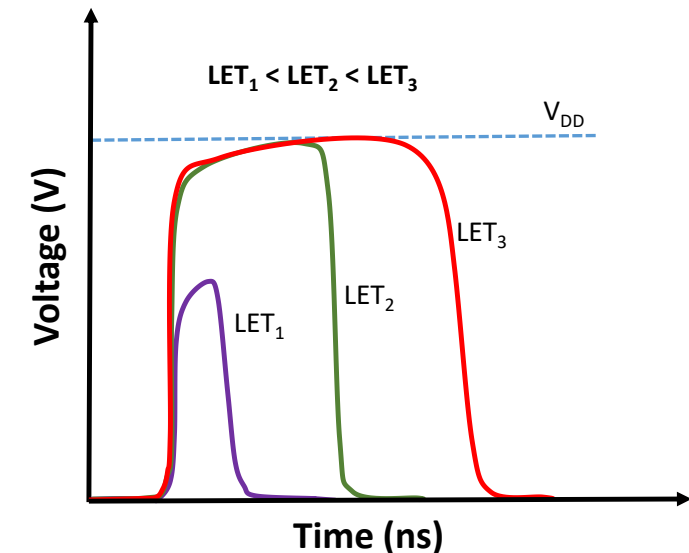
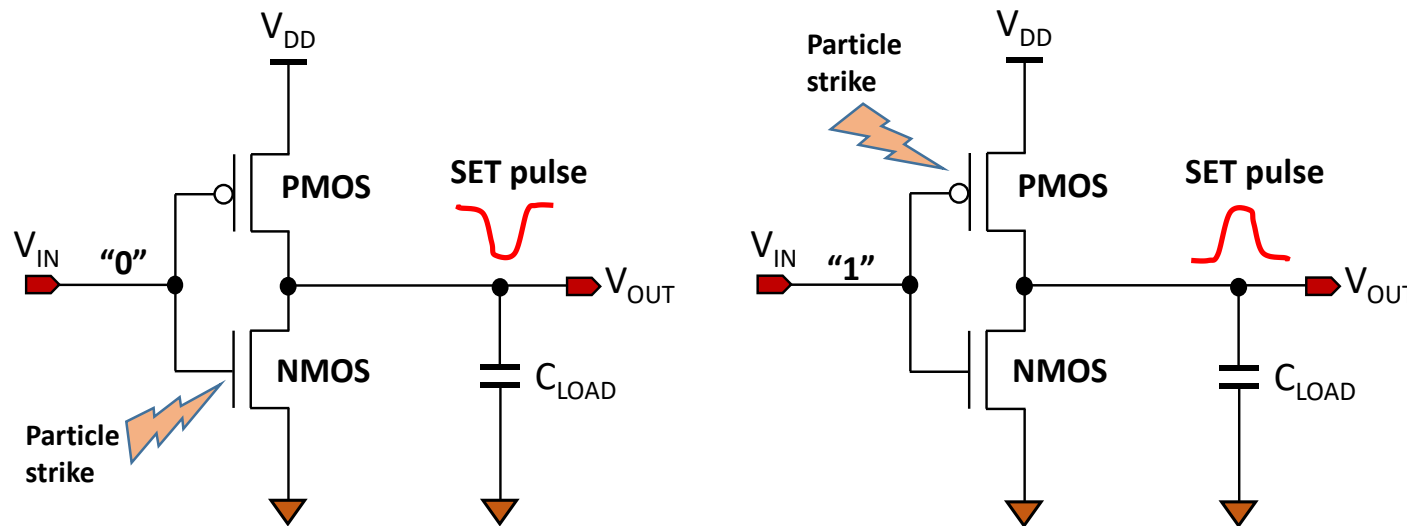


1. Introduction to SET Effects



SET generation

- If the charge released as a result of particle strike exceeds the critical charge of the circuit node, a SET voltage pulse will be formed
- Generated SET pulse width is in the order of **tens to hundreds picoseconds**, and it depends on particle Linear Energy Transfer (LET) and technology/design/operating parameters

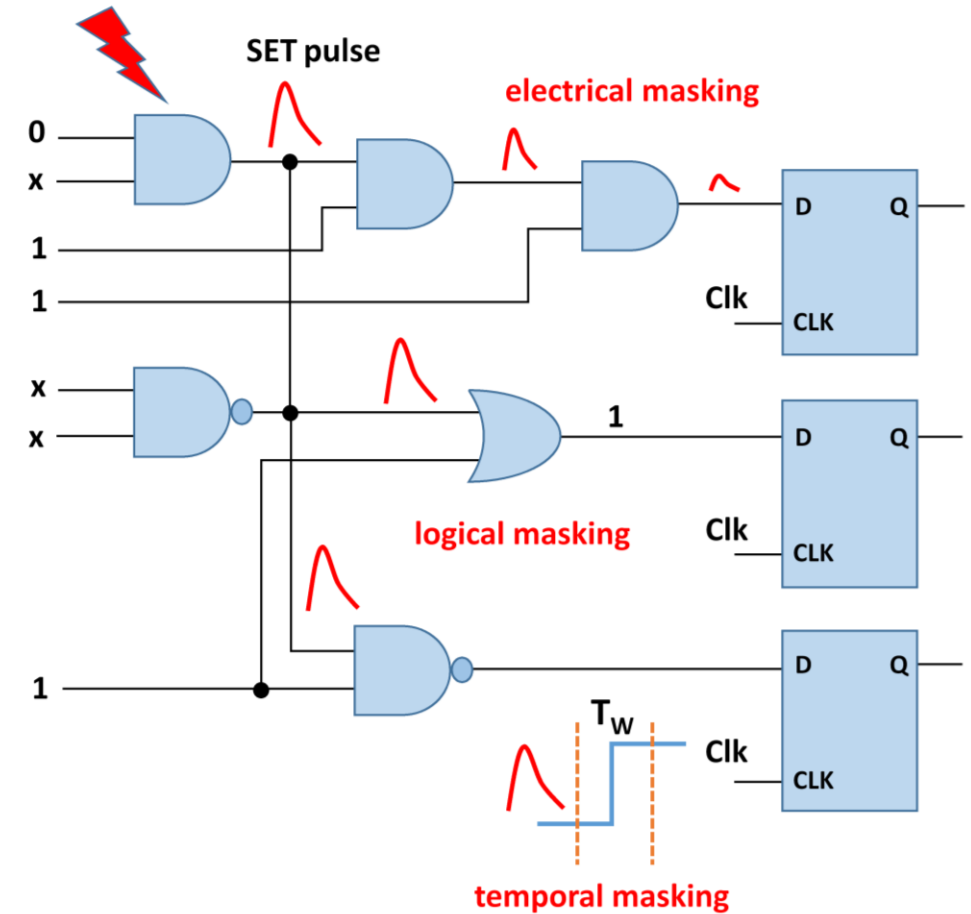


1. Introduction to SET Effects



SET propagation

- SET propagation depends on input pulse width, circuit design and operating parameters
- SETs longer than propagation delay of logic gates may propagate through the circuit
- SETs may be masked by 3 masking effects: electrical, logical and temporal masking
- SET pulse width may increase during propagation due to Propagation-induced Pulse Broadening (PIPB)



1. Introduction to SET Effects



—○ Basic SET sensitivity metrics

- SET generation metrics: critical charge and generated SET pulse width
- SET propagation metrics: propagated SET pulse width
- Combinational Soft Error Rate (SER) – number of SET-induced soft errors in a given time interval

$$SER = \sum_{i=1}^N SER_{NOMINAL}(i) \cdot SER_{DERATING}(i)$$

N = number of components in the system

$$SER_{NOMINAL} = k \cdot Flux \cdot Area \cdot e^{-\frac{Q_{CRIT}}{Q_s}}$$

$$SER_{DERATING} = Logical_{DER} \cdot Electrical_{DER} \cdot Timing_{DER}$$

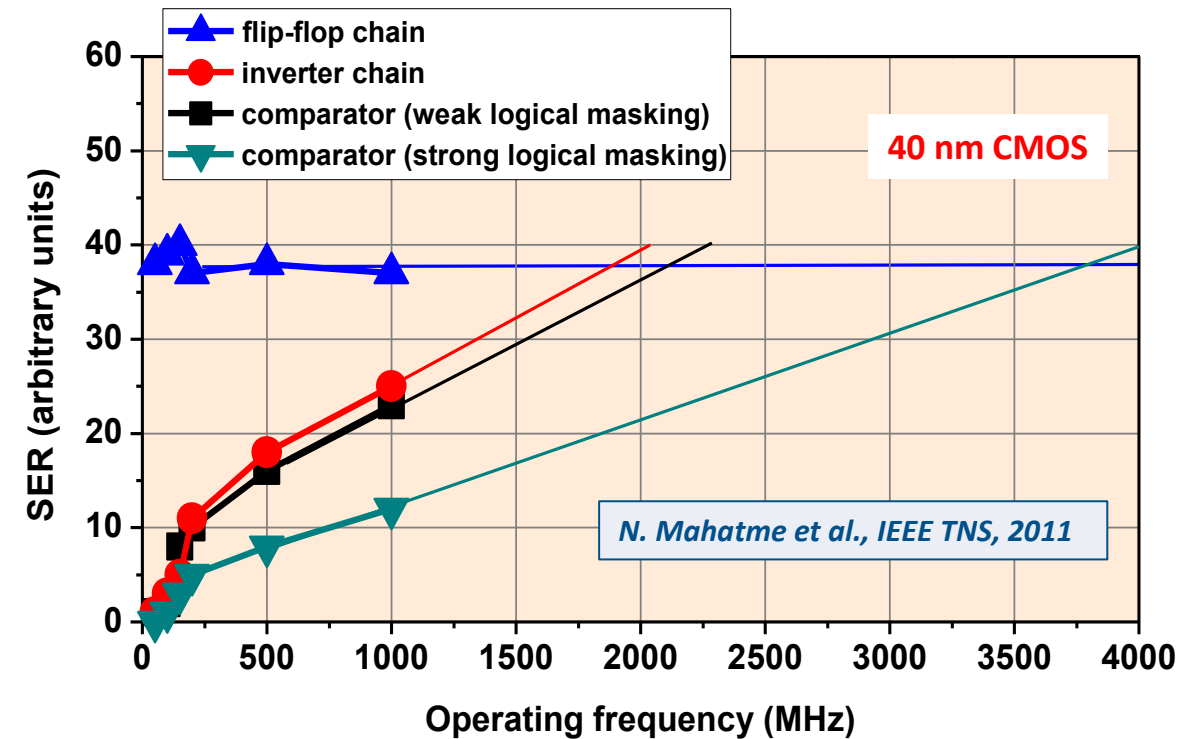
1. Introduction to SET Effects



—○ Contribution of SETs to the total Soft Error Rate (SER) of digital circuits increases with technology scaling trends

- Decrease in transistor size
- Decrease in supply voltage
- Decrease in logic path length
- Increase in clock frequency

At GHz clock frequencies, SER of simple combinational circuits may be comparable or larger than SET of flip-flops

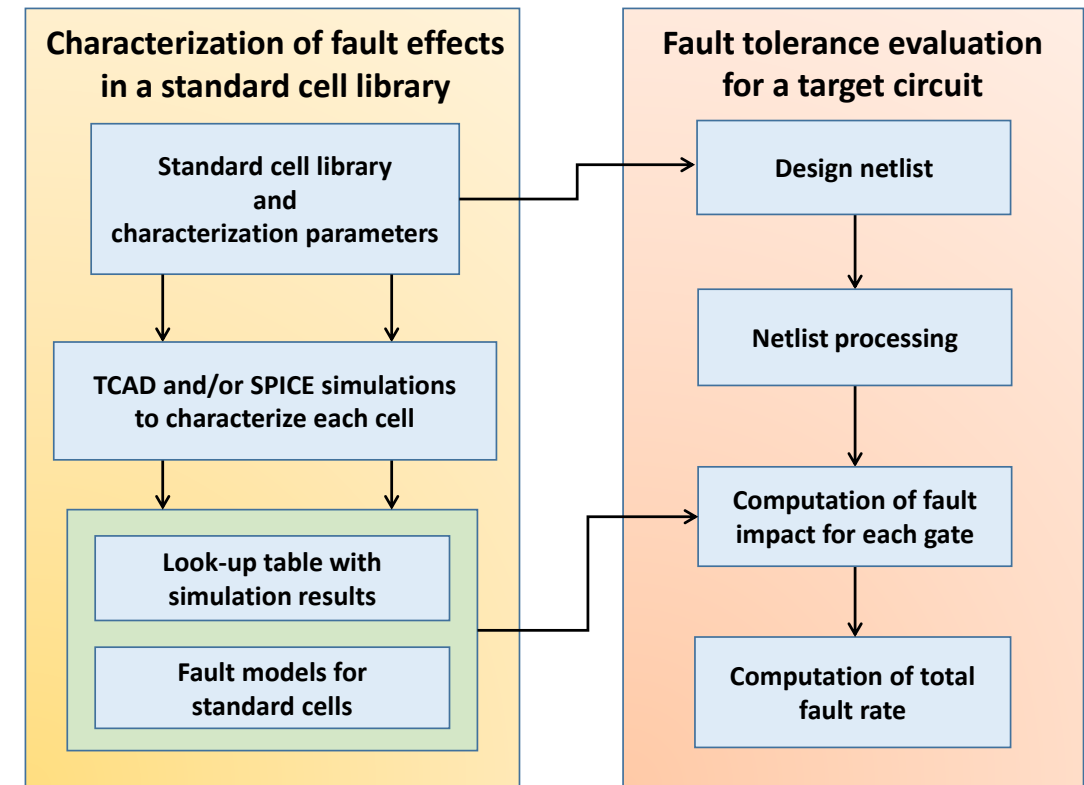


2. SET Characterization Methodology



—○ SET analysis with combined simulations and analytical methods

- Simulations are used to characterize fault effects for a given technology and standard cell library, and this process is performed only once
- Analytical methods are used to analyze fault tolerance of a complex design
- Benefits
 - Accurate analysis of fault effects
 - Low runtime (fast analysis)

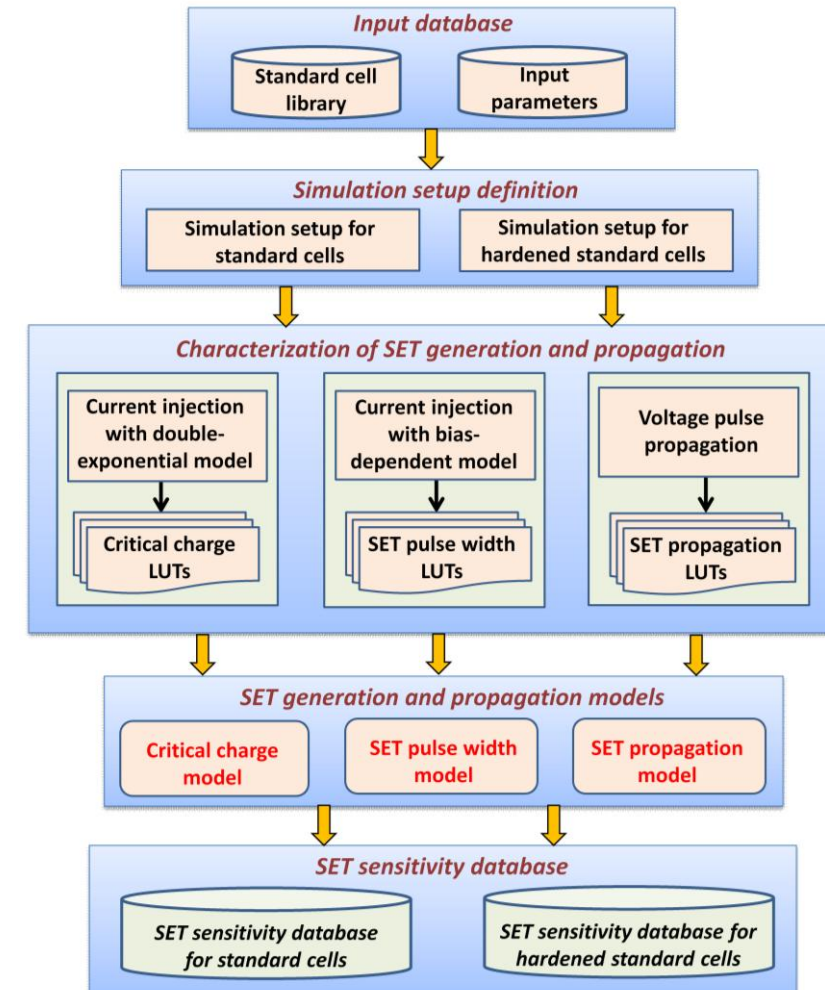


2. SET Characterization Methodology



— Joint characterization of SET sensitivity of standard cells and their hardened variants

- SPICE simulations are used to analyze SET sensitivity of each standard cell and its hardened variants in a given technology
- SET sensitivity is analyzed as a function of various parameters:
 - ❖ Irradiation parameters – particle LET, SET current/voltage parameters
 - ❖ Design parameters – target gate size, load size, wire capacitance
 - ❖ Operating parameters – supply voltage, temperature, input vectors
- Simulation results are stored in look-up tables (LUTs)
- Analytical models for SET sensitivity metrics are derived from LUTs



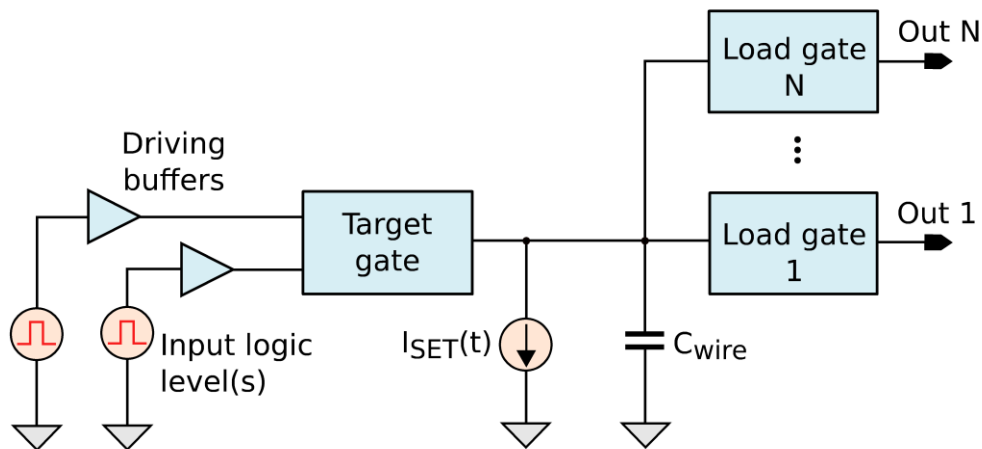
2. SET Characterization Methodology



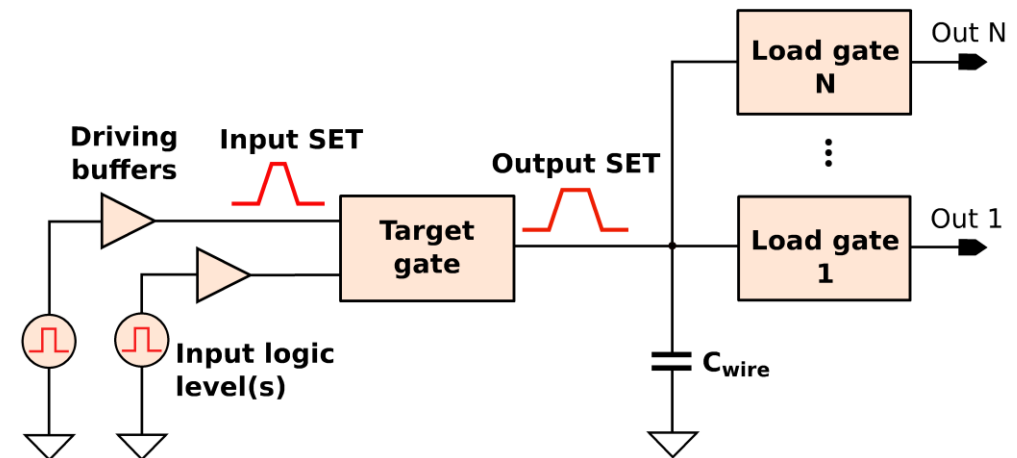
SET generation and SET propagation simulation setups

- Double-exponential current source is used to determine critical charge
- Bias-dependent current model is used to determine generated SET pulse width
- Trapezoidal voltage pulse is used to evaluate SET propagation

SET generation simulation setup



SET propagation simulation setup



2. SET Characterization Methodology



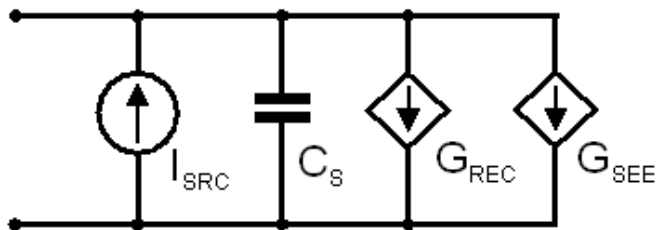
—○ Bias-dependent current model (by Kaupilla et al., *IEEE TNS*, 2009)

- Composed of double-exponential current source and two voltage-controlled current sources
- Takes into account the plateau region in current pulse that occurs for high LET values
- User-defined parameters: LET, rise and fall time for current pulse

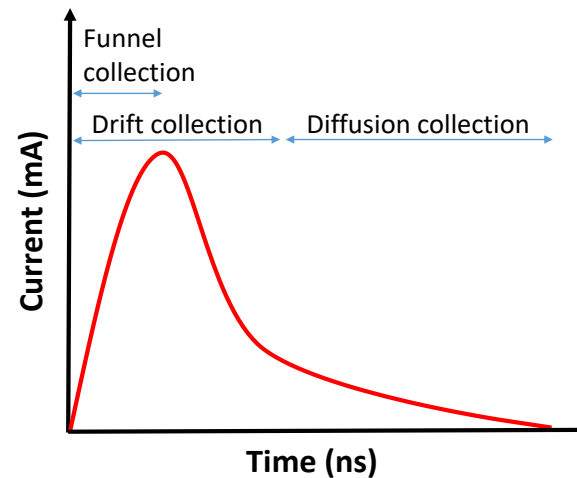
Double-exponential current model

$$I_{SRC}(t) = \frac{Q_{COLL}}{\tau_f - \tau_r} (e^{-t/\tau_f} - e^{-t/\tau_r})$$

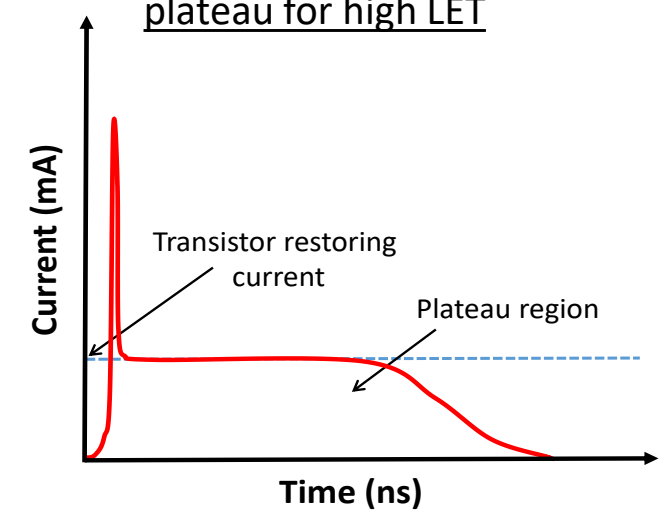
Bias-dependent current model



Double-exponential current pulse



Current pulse with plateau for high LET

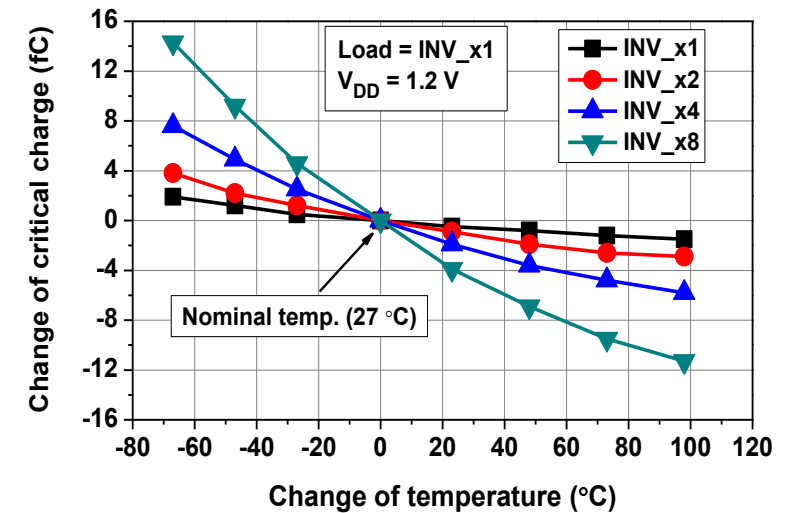
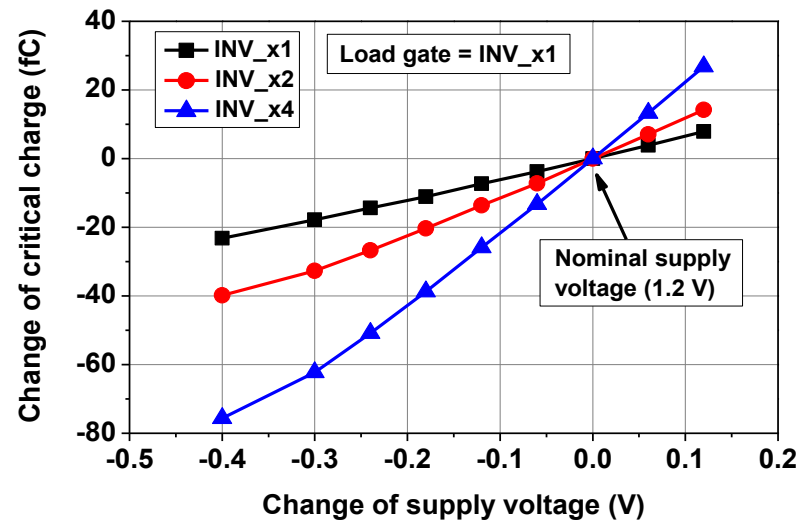
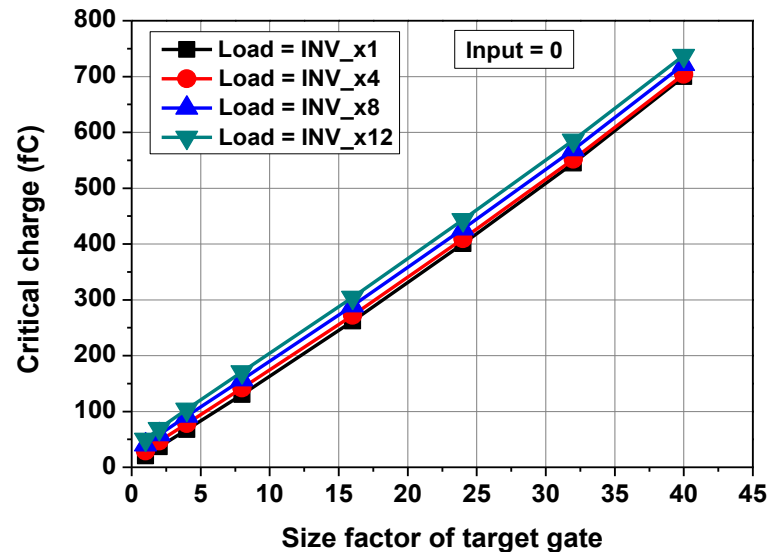


3. SET Characterization for IHP's 130nm Standard Cells



Critical charge

- Q_{CRIT} increases with the size of target gate and load gate, where target gate has stronger impact than load gate(s)
- A logic gate is more robust to particle strikes at higher supply voltage and lower temperature

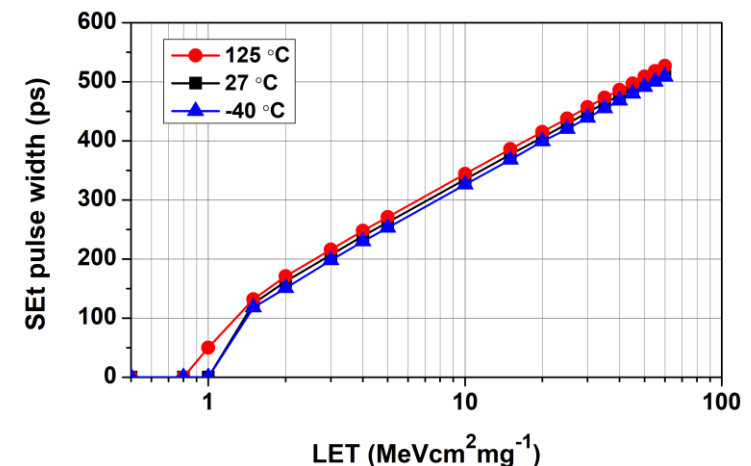
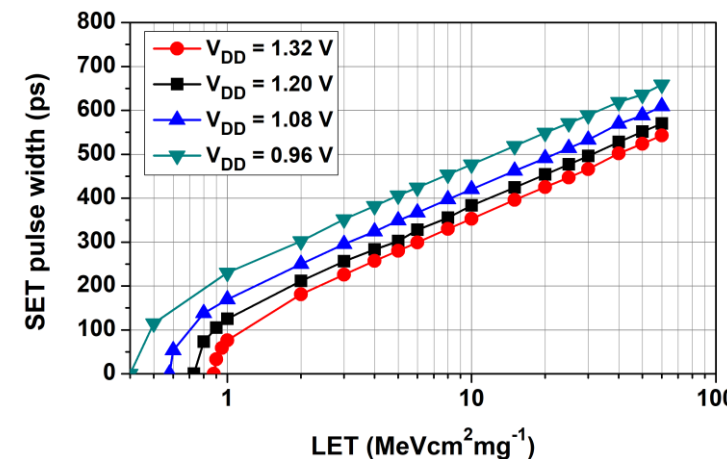
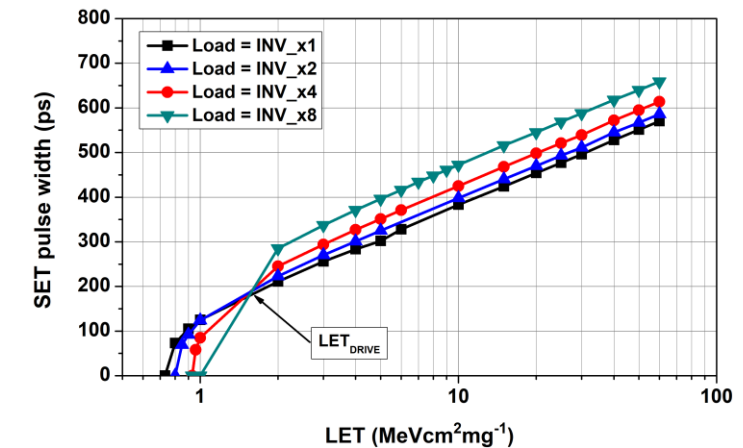
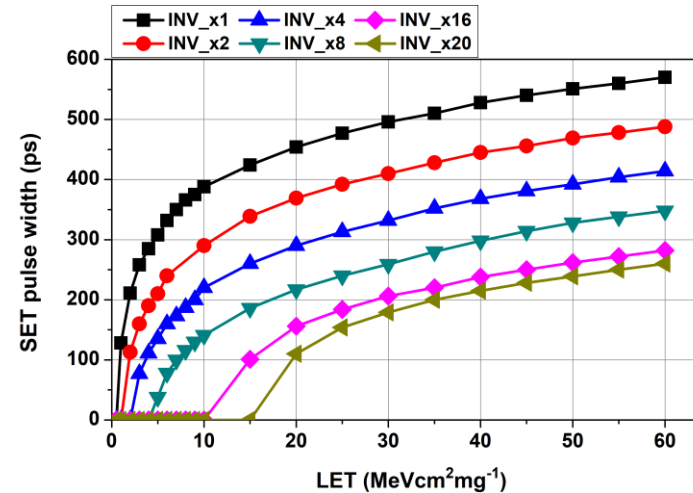


3. SET Characterization for IHP's 130nm Standard Cells



Generated SET pulse width

- SET pulse width increases with LET
- Increase of gate size reduces the SET pulse width
- Large load increases the SET pulse width for higher LET
- V_{DD} increase leads to a decrease in SET pulse width
- T_{EMP} decrease leads to a decrease in SET pulse width

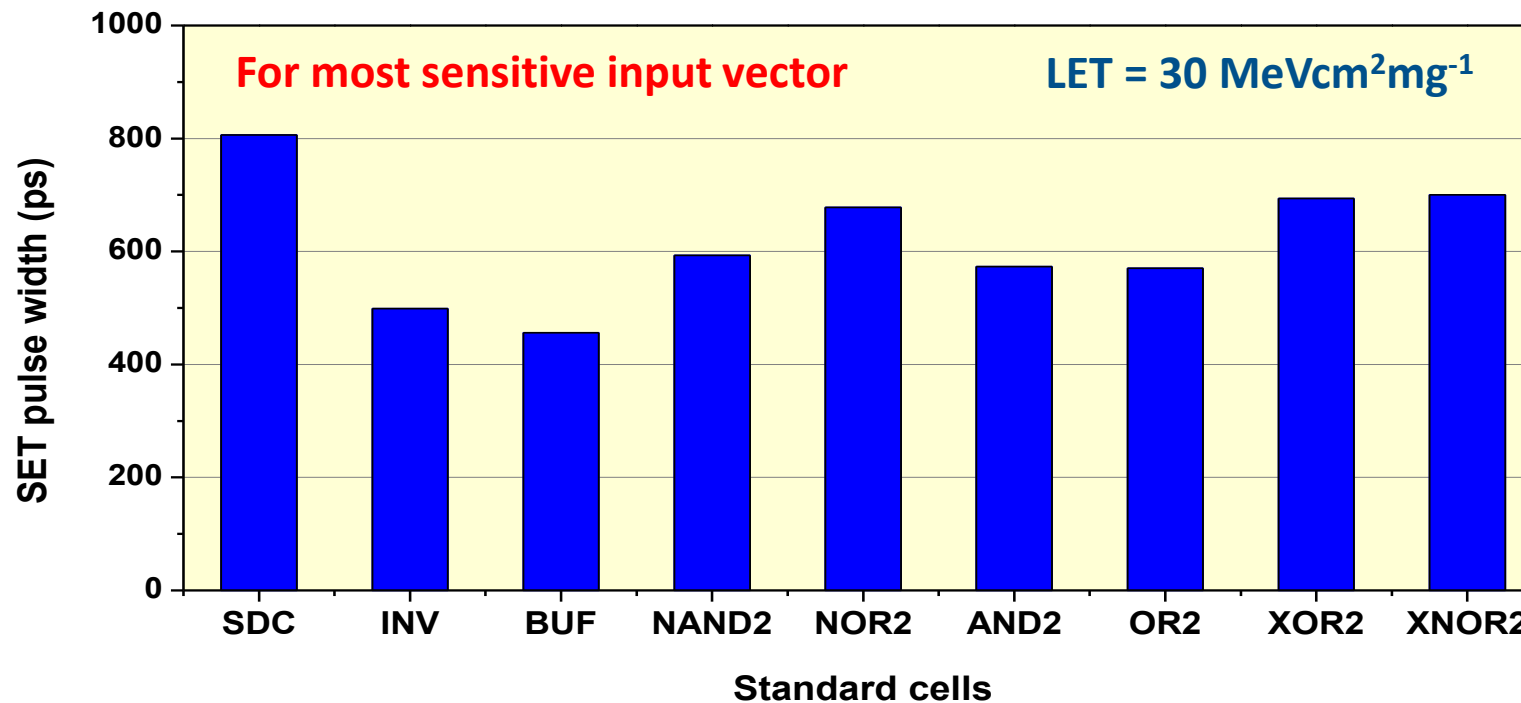


3. SET Characterization for IHP's 130nm Standard Cells



Generated SET pulse width - comparison

- SET pulse width may vary by several hundred picoseconds depending on gate type



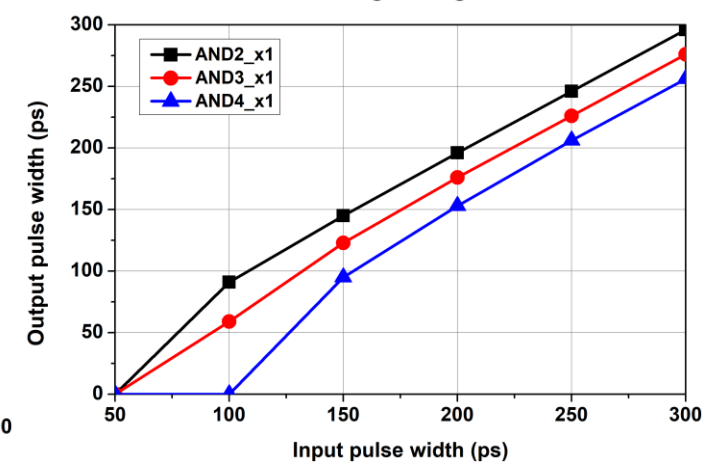
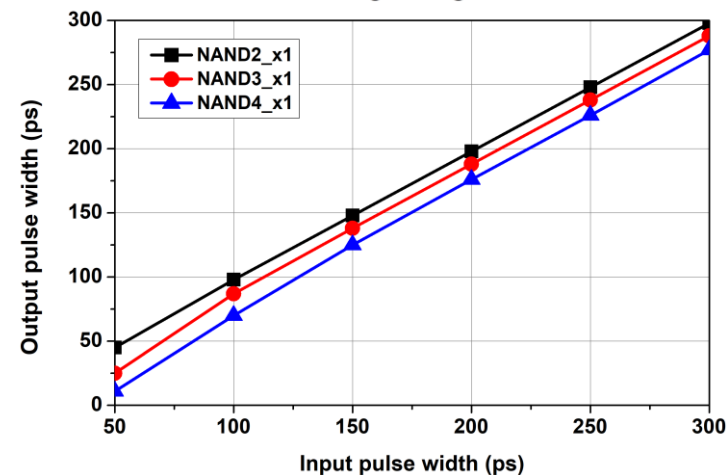
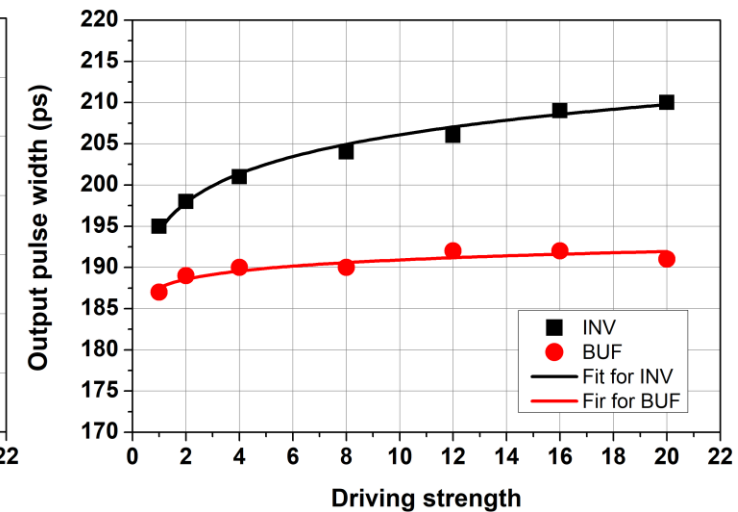
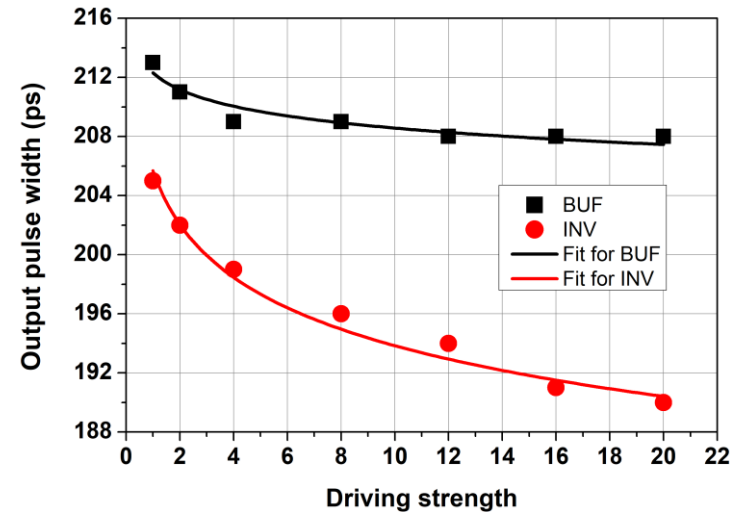
3. SET Characterization for IHP's 130nm Standard Cells



Propagated SET pulse width

- Increases or decreases with respect to input pulse width, depending on input pulse polarity
- Varies significantly depending on load capacitance, supply voltage, and temperature

More complex gates have better SET filtering capability



3. SET Characterization for IHP's 130nm Standard Cells



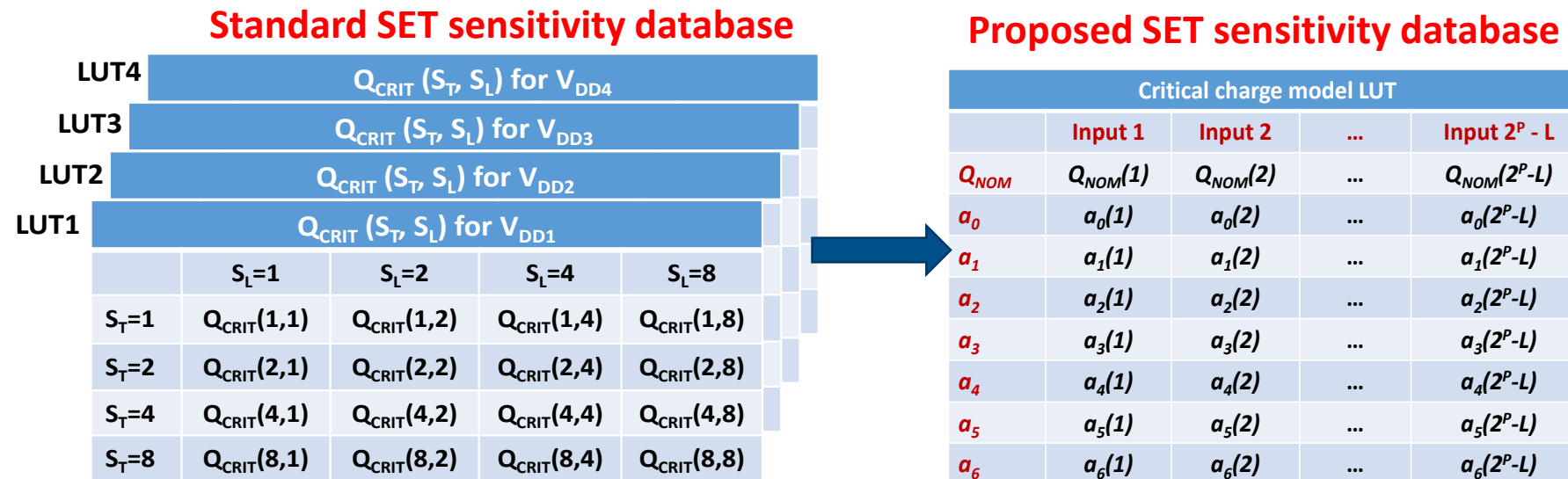
- Propagated SET pulse width – Short combinational paths may cause significant SET broadening

10-gate combinational paths (all gates are with driving strength x1)	Output pulse width (ps)					
	Positive input pulse = 200 ps			Negative input pulse = 200 ps		
	LVT	TVT	HVT	LVT	TVT	HVT
INV	208	206	204	195	196	197
BUF	367	322	293	0	68	108
NAND2	201	201	201	203	204	204
AND2	166	152	134	237	250	268
NOR2	223	216	214	151	176	185
OR2	925	748	645	0	0	0
Alternating OR2 and AND2	542	447	387	0	0	0
Alternating AND3 and OR4	499	416	359	0	0	0
Alternating NAND2 and NOR3	667	563	506	0	0	0
Alternating XNOR3 and NOR2	0	0	0	173	243	252

4. SET Sensitivity Prediction with Fitting Models



- By fitting the simulation results with standard fitting models, analytical models for SET sensitivity metrics can be derived
- Storing the model parameters in LUTs reduces the characterization database



4. SET Sensitivity Prediction with Fitting Models



—○ SET sensitivity of each gate can be expressed with 3 LUTs

- Critical charge LUT
- Generated SET pulse width LUT
- Propagated SET pulse width LUT

Critical charge model LUT				
	Input 1	Input 2	...	Input $2^P - L$
Q_{NOM}	$Q_{NOM}(1)$	$Q_{NOM}(2)$	...	$Q_{NOM}(2^P - L)$
a_0	$a_0(1)$	$a_0(2)$	...	$a_0(2^P - L)$
a_1	$a_1(1)$	$a_1(2)$	...	$a_1(2^P - L)$
a_2	$a_2(1)$	$a_2(2)$	...	$a_2(2^P - L)$
a_3	$a_3(1)$	$a_3(2)$	...	$a_3(2^P - L)$
a_4	$a_4(1)$	$a_4(2)$	...	$a_4(2^P - L)$
a_5	$a_5(1)$	$a_5(2)$	...	$a_5(2^P - L)$
a_6	$a_6(1)$	$a_6(2)$	...	$a_6(2^P - L)$

Generated SET pulse width model LUT				
	Input 1	Input 2	...	Input $2^P - L$
LET_{DRIVE}	$LET_{DRIVE}(1)$	$LET_{DRIVE}(2)$	...	$LET_{DRIVE}(2^P - L)$
b_0	$b_0(1)$	$b_0(2)$	...	$b_0(2^P - L)$
b_1	$b_1(1)$	$b_1(2)$	...	$b_1(2^P - L)$
b_2	$b_2(1)$	$b_2(2)$	...	$b_2(2^P - L)$
b_3	$b_3(1)$	$b_3(2)$	...	$b_3(2^P - L)$
b_4	$b_4(1)$	$b_4(2)$	...	$b_4(2^P - L)$
b_5	$b_5(1)$	$b_5(2)$	...	$b_5(2^P - L)$
b_6	$b_6(1)$	$b_6(2)$	...	$b_6(2^P - L)$
b_7	$b_7(1)$	$b_7(2)$	...	$b_7(2^P - L)$
b_8	$b_8(1)$	$b_8(2)$	...	$b_8(2^P - L)$
b_9	$b_9(1)$	$b_9(2)$	...	$b_9(2^P - L)$

Propagated SET pulse width model LUT				
	Input 1	Input 2	...	Input P
c_0	$c_0(1)$	$c_0(2)$	...	$c_0(P)$
c_1	$c_1(1)$	$c_1(2)$	...	$c_1(P)$
c_2	$c_2(1)$	$c_2(2)$	...	$c_2(P)$
c_3	$c_3(1)$	$c_3(2)$	...	$c_3(P)$
c_4	$c_4(1)$	$c_4(2)$	...	$c_4(P)$
c_5	$c_5(1)$	$c_5(2)$	...	$c_5(P)$
c_6	$c_6(1)$	$c_6(2)$	...	$c_6(P)$

4. SET Sensitivity Prediction with Fitting Models



—○ General SET sensitivity model – sum of contributing parameters

- Impact of each parameter can be evaluated

$$\text{SET_metric} = \text{SET_metric_nominal} + \sum_{i=1}^N f_i \cdot (K_i - K_{iNOM})$$

f_i = fitting function

K_i = contributing parameter (e.g. size factor)

4. SET Sensitivity Prediction with Fitting Models



- Models for critical charge, generated SET pulse width and propagated SET pulse width

Critical charge model (8 fitting parameters per cell)

$$Q_{CRIT} = Q_{NOM} + f(S_T) + f(S_L) + f(C_L) + f(V_{DD}) + f(T_{EMP}) + f_{ERROR}$$

Generated SET pulse width model (12 fitting parameters per cell)

$$T_{SET} = f(LET, S_T = 1) + f(S_T = n) + f(S_L, C_L) + f(V_{DD}) + f(T_{EMP})$$

Propagated SET pulse width model (7 fitting parameters per cell)

$$T_{OUT} = T_{IN} \pm \Delta\tau = T_{IN} \pm c_0 \pm f(S_T) \pm f(C_L) \pm f(V_{DD}) \pm f(T_{EMP})$$

Average relative error for each model (with respect to SPICE) is less than 5 %.

Maximum error goes up 20%, for corner values

Fitting models are based on simplifications and do not take into account all dependencies

5. SET Sensitivity Prediction with ML Models



—○ SET generation and propagation prediction with ML

- ML models are a promising solution for modeling complex dependencies
- Use of ML to aging and soft errors is investigated intensively in past years
- Very few papers address SET prediction with ML

Main approach: Train existing ML models with simulation datasets

1. Data pre-processing and machine learning (regression) model selection
2. Model training and parameter optimization
3. Model evaluation and assessment of model performance



5. SET Sensitivity Prediction with ML Models



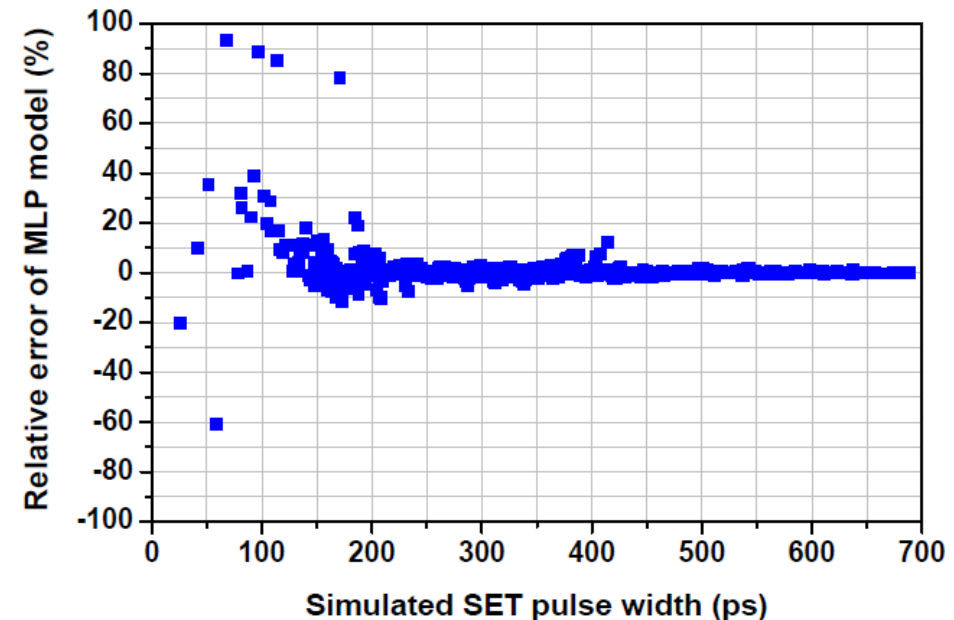
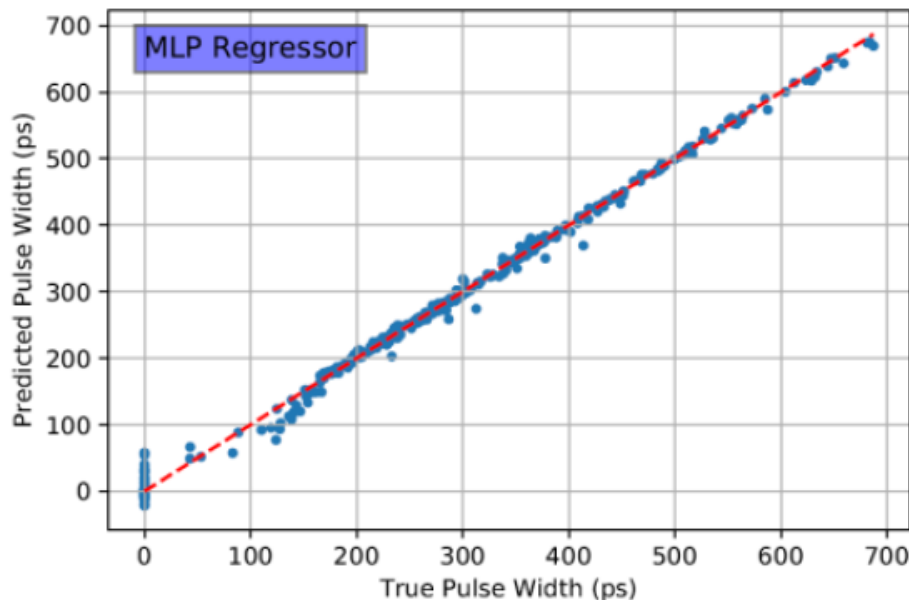
—○ SET generation prediction

- 6 models have been studied: Linear Regression, Polynomial Regression, Support Vector Machine, Decision Tree, Random Forest, and Multilayer Perceptron
- INV cell from 130 nm library was studied
- 2560 SET pulse width results from SPICE simulations
- Analyzed parameters: target gate size, load gate size, Temp, Vdd, LET
- 60% training dataset, 40% validation dataset
- Evaluation metrics. MAE, RMSE, R^2

5. SET Sensitivity Prediction with ML Models



- MLP has shown the best results for SET generation prediction (R^2 above 99%)
- Linear regression has worst prediction accuracy for SET generation (R^2 below 80%)



5. SET Sensitivity Prediction with ML Models



—○ SET propagation prediction

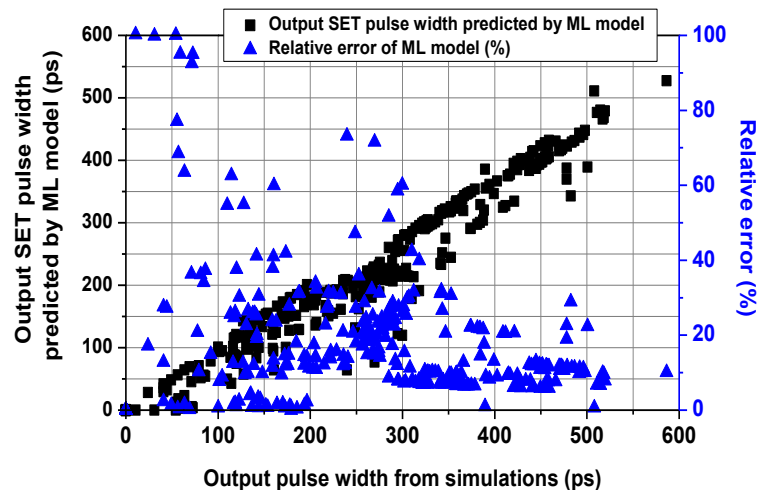
- 10 ML models have been studied: Linear Regression, Ridge Regression, Lasso Regression, Random Forest, Gradient Boosting, Support Vector Machine, Multilayer Perceptron, XGBoost, CatBoost, LightGBM
- INV, NAND2 and NOR2 gates from 130 nm standard cell library have been analyzed
- 25600 values for INV and 12800 values for NAND and NOR gates have been obtained from Spectre simulations
- Analyzed parameters: input pulse width and polarity, target and load gate sizes, Vdd and Temp
- Simulation dataset was divided into two datasets: 70% training dataset, 30% validation dataset
- ML valuation metrics: MAE, RMSE, R^2

5. SET Sensitivity Prediction with ML Models

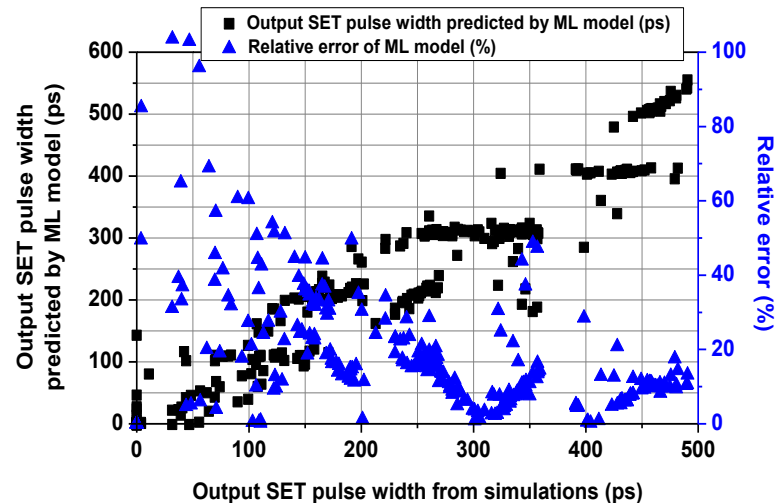


- Different ML models have shown best accuracy for SET propagation prediction
- In all cases, R^2 was above 99% for best model
- However, relative error is high for prediction of short SET propagation

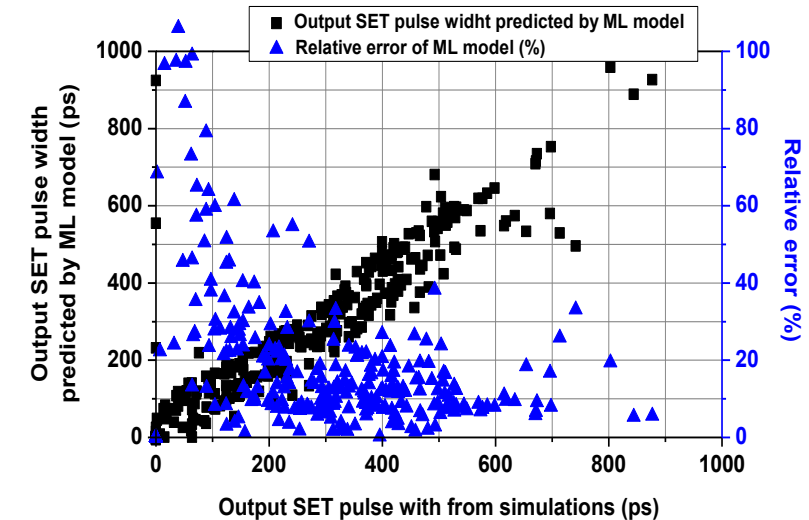
INV gate – XGBoost model



NAND2 gate – CatBoost model



NOR2 gate – CatBoost model



5. SET Sensitivity Prediction with ML Models



—○ SET propagation prediction for short combinational paths (less than 10 gates)

Settings	Output SET pulse width from ML model (ps)	Output SET pulse width from SPICE simulations (ps)	Relative error (%)
Path 1, Vdd=1.2V, Temp = 50 °C, Input PW = 150 ps (positive pulse)	109.4	165.7	34 %
Path 1, Vdd=1.2V, Temp = 50 °C, Input PW = 150 ps (negative pulse)	110.5	134.4	17.8 %
Path 1, Vdd=1.1V, Temp = 80 °C, Input PW = 380 ps (positive pulse)	510.2	400.6	27.4 %
Path 1, Vdd=1.1V, Temp = 80 °C, Input PW = 380 ps (negative pulse)	511.7	367.1	39.4 %
Path 2, Vdd=1.2V, Temp = -20 °C, Input PW = 240 ps (positive pulse)	215.4	302.7	28.8 %
Path 2, Vdd=1.2V, Temp = -20 °C, Input PW = 240 ps (negative pulse)	204.6	181.9	12.5%
Path 2, Vdd=1 V, Temp = 100 °C, Input PW = 480 ps (positive pulse)	517.7	588.3	12 %
Path 2, Vdd=1 V, Temp = 100 °C, Input PW = 480 ps (negative pulse)	502.3	381.3	31.7 %

6. Conclusion



- **Characterization of SET sensitivity of standard cells is essential for the rad-hard design**
- **SET sensitivity of a logic gate in a given technology is strongly influenced by a combined impact of design, operating and irradiation parameters**
- **Analytical models for SET sensitivity reduce the characterization database and runtime for analysis of a complex circuit**
- **Future work**
 - Derivation of more accurate SET generation and propagation models
 - Integration of SET sensitivity models into an automated toolflow for analysis of complex designs
 - Analysis of combined impact of multiple fault types



Thank you for your attention!

IHP GmbH – Innovations for High Performance Microelectronics

Im Technologiepark 25

15236 Frankfurt (Oder)

Tel.: +49 (0) 335 5625 527

E-Mail: andjelkovic@ihp-microelectronics.com

